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NEWS 9	JUN 16	WPI First View (File WPIFV) will no longer be available after July 30, 2010
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NEWS 11	JUN 18	CAS and FIZ Karlsruhe announce plans for a new STN platform
NEWS 12	JUN 18	IPC codes have been added to the INSPEC backfile (1969-2009)
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NEWS 18	JUL 26	CAS coverage of global patent authorities has expanded to 61 with the addition of Costa Rica
NEWS 19	SEP 15	MEDLINE Cited References provide additional revelant records with no additional searching.
NEWS 20	OCT 04	Removal of Pre-IPC 8 data fields streamlines displays in USPATFULL, USPAT2, and USPATOLD.
NEWS 21	OCT 04	Precision of EMBASE searching enhanced with new chemical name field

NEWS 22 OCT 06 Increase your retrieval consistency with new formats for Taiwanese application numbers in CA/CAplus.

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DICTIONARY FILE UPDATES: 18 OCT 2010 HIGHEST RN 1246494-44-9

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http://www.cas.org/support/stngen/stndoc/properties.html

=> S 64404-02-4
L1 0 64404-02-4

=> S SARTOMER 349

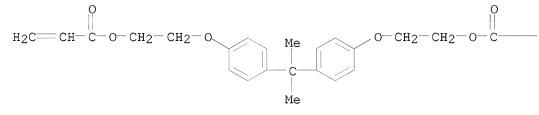
```
          270 SARTOMER
         8870 349
L2          6 SARTOMER 349
               (SARTOMER(W)349)

=> S SARTOMER 349/CRN
L3          0 SARTOMER 349/CRN

=> S SARTOMER 349/CN
L4          1 SARTOMER 349/CN

=> D ALL

L4   ANSWER 1 OF 1  REGISTRY  COPYRIGHT 2010 ACS on STN
RN   24447-78-7  REGISTRY
ED   Entered STN:  16 Nov 1984
CN   2-Propenoic acid, 1,1'-[(1-methylethylidene)bis(4,1-phenyleneoxy-2,1-
     ethanediyl)] ester  (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN   2-Propenoic acid, (1-methylethylidene)bis(4,1-phenyleneoxy-2,1-ethanediyl)
     ester (9CI)
CN   Acrylic acid, diester with 2,2'-[isopropylidenebis(p-
     phenyleneoxy)]diethanol (8CI)
CN   Ethanol, 2,2'-[isopropylidenebis(p-phenyleneoxy)]di-, diacrylate (8CI)
OTHER NAMES:
CN   2,2-Bis(4-acryloxyethoxyphenyl)propane
CN   2,2-Bis[4-(2-acryloyloxyethoxy)phenyl]propane
CN   Bisphenol A bis(2-hydroxyethyl ether) diacrylate
CN   Bisphenol A bis[2-(acryloyloxy)ethyl] ether
CN   Bisphenol A di(acryloyloxyethyl) ether
CN   Bis[1-(2-acryloxy)-p-ethoxyphenyldimethylmethane]
CN   BR 800
CN   EB 952
CN   FM 300
CN   Kayarad FM 300
CN   Sartomer 349
CN   Sartomer SR 349
CN   Setalin AM 548
CN   Setalux UV 2246
CN   Setalux UV 2248
CN   SR 349
DR   58458-00-7, 130340-91-9, 143550-30-5, 208666-27-7
MF   C25 H28 O6
CI   COM
LC   STN Files:   CA, CAPLUS, CASREACT, CHEMCATS, CHEMLIST, CIN, CSCHEM,
       IFICDB, IFIPAT, IFIUDB, MSDS-OHS, PIRA, PROMT, TOXCENTER, USPAT2,
       USPATFULL, USPATOLD
     Other Sources:   DSL**, EINECS**, TSCA**
        (**Enter CHEMLIST File for up-to-date regulatory information)
DT.CA  CAplus document type:  Conference; Journal; Patent; Report
RL.P   Roles from patents:  BIOL (Biological study); PREP (Preparation); PROC
       (Process); PRP (Properties); RACT (Reactant or reagent); USES (Uses)
RLD.P  Roles for non-specific derivatives from patents:  BIOL (Biological
       study); PREP (Preparation); PROC (Process); PRP (Properties); USES
       (Uses)
RL.NP  Roles from non-patents:  ANST (Analytical study); BIOL (Biological
       study); CMBI (Combinatorial study); OCCU (Occurrence); PREP
```

(Preparation); PROC (Process); PRP (Properties); RACT (Reactant or reagent); USES (Uses)
RLD.NP Roles for non-specific derivatives from non-patents: PREP (Preparation); PROC (Process); PRP (Properties); USES (Uses)

Ring System Data

Elemental Analysis	Elemental Sequence	Size of the Rings	Ring System Formula	Ring Identifier	RID Occurrence Count
EA	ES	SZ	RF	RID	
C6	C6	6	C6	46.150.18	2

PAGE 1-A



PAGE 1-B

Experimental Properties (EPROP)

PROPERTY (CODE)	VALUE	NOTE
IR Absorption Spectra	Spectrum	(1) BIORAD

(1) Infrared spectral data from the Bio-Rad/Sadtler IR Data Collection was obtained from Bio-Rad Laboratories, Philadelphia, PA (US). Copyright (C) Bio-Rad Laboratories. All Rights Reserved.

Experimental Property Tags (ETAG)

PROPERTY	NOTE
Viscosity	(1) CAS

(1) Tarzi, O. I.; Journal of Polymer Science, Part A: Polymer Chemistry 2010 V48(12) P2594-2603 CAPLUS

Predicted Properties (PPROP)

PROPERTY (CODE)	VALUE	CONDITION	NOTE
Bioconc. Factor (BCF)	9102.35	pH 1 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 2 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 3 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 4 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 5 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 6 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 7 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 8 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 9 25 deg C	(1)
Bioconc. Factor (BCF)	9102.35	pH 10 25 deg C	(1)
Boiling Point (BP)	554.3+/-50.0 deg C	760 Torr	(1)
Density (DEN)	1.117+/-0.06 g/cm**3	20 deg C	(1)
		760 Torr	
Enthalpy of Vap. (HVAP)	83.53+/-3.0 kJ/mol	760 Torr	(1)
Flash Point (FP)	237.4+/-30.2 deg C		(1)
Freely Rotatable Bonds (FRB)	14		(1)
H acceptors (HAC)	6		(1)
H donors (HD)	0		(1)
Hydrogen Donors/Acceptors Sum (HDAS)	6		(1)
Koc (KOC)	23743.88	pH 1 25 deg C	(1)
Koc (KOC)	23743.88	pH 2 25 deg C	(1)
Koc (KOC)	23743.88	pH 3 25 deg C	(1)
Koc (KOC)	23743.88	pH 4 25 deg C	(1)
Koc (KOC)	23743.88	pH 5 25 deg C	(1)
Koc (KOC)	23743.88	pH 6 25 deg C	(1)
Koc (KOC)	23743.88	pH 7 25 deg C	(1)
Koc (KOC)	23743.88	pH 8 25 deg C	(1)
Koc (KOC)	23743.88	pH 9 25 deg C	(1)
Koc (KOC)	23743.88	pH 10 25 deg C	(1)
LOGD (LOGD)	5.51	pH 1 25 deg C	(1)
LOGD (LOGD)	5.51	pH 2 25 deg C	(1)
LOGD (LOGD)	5.51	pH 3 25 deg C	(1)
LOGD (LOGD)	5.51	pH 4 25 deg C	(1)
LOGD (LOGD)	5.51	pH 5 25 deg C	(1)
LOGD (LOGD)	5.51	pH 6 25 deg C	(1)
LOGD (LOGD)	5.51	pH 7 25 deg C	(1)
LOGD (LOGD)	5.51	pH 8 25 deg C	(1)
LOGD (LOGD)	5.51	pH 9 25 deg C	(1)
LOGD (LOGD)	5.51	pH 10 25 deg C	(1)
LOGP (LOGP)	5.512+/-0.377	25 deg C	(1)
Mass Intrinsic Solubility (ISLB.MASS)	0.0016 g/L	25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 1 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 2 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 3 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 4 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 5 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 6 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 7 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 8 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 9 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	pH 10 25 deg C	(1)
Mass Solubility (SLB.MASS)	0.0016 g/L	Unbuffered Water pH 7.00	(1)

	|	|25 deg C	|
Molar Intrinsic Solubility (ISLB.MOL)	|0.0000038 mol/L	|25 deg C	|(1)
	|	|	|
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 1 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 2 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 3 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 4 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 5 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 6 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 7 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 8 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 9 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|pH 10 25 deg C	|(1)
Molar Solubility (SLB.MOL)	|0.0000038 mol/L	|Unbuffered Water	|(1)
	|	|pH 7.00	|
	|	|25 deg C	|
Molar Volume (MVOL)	|379.9+/-3.0 cm**3/mol	|20 deg C	|(1)
	|	|760 Torr	|
Molecular Weight (MW)	|424.49	|	|(1)
Polar Surface Area (PSA)	|71.06 A**2	|	|(1)
Vapor Pressure (VP)	|2.51E-12 Torr	|25 deg C	|(1)

(1) Calculated using Advanced Chemistry Development (ACD/Labs) Software V11.02 ((C) 1994-2010 ACD/Labs)

See HELP PROPERTIES for information about property data sources in REGISTRY.

204 REFERENCES IN FILE CA (1907 TO DATE)
27 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
205 REFERENCES IN FILE CAPLUS (1907 TO DATE)

REFERENCE 1

AN 153:383443 CA
TI Visible light photoinitiating systems: toward a good control of the photopolymerization efficiency
AU Ibrahim, A.; Ley, C.; Tarzi, O. I.; Fouassier, J. P.; Allonas, X.
CS Department of Photochemistry, CNRS, ENSCMu, University of Haute Alsace, Mulhouse, 68093, Fr.
SO Journal of Photopolymer Science and Technology (2010), 23(1), 101-108 CODEN: JSTEEW; ISSN: 0914-9244
PB Conference of Photopolymer Science and Technology
DT Journal
LA English
CC 35-4 (Chemistry of Synthetic High Polymers)
Section cross-reference(s): 36, 41, 67, 74
AB This paper discusses the photochem. of three-component photoinitiating systems (3K-PIS) for free radical photopolymn. and the efforts made during the last decades to propose efficient systems applied to the laser imaging area. A special focus is devoted to a new 3K-PIS working in the green region. It is based on a pyrromethene dye which is reduced or oxidized by a coinitiator. A third redox component is used that leads to the recovery of the initial dye and the formation of addnl. initiating species, preventing a fast photobleaching of the dye. The beneficial effect on the photopolymn. rates and the final monomer conversion is clearly noticed. Laser flash photolysis was used to understand the reaction mechanisms, and detailed photopolymn. kinetics allow the study of polymeric network

formation.
ST visible light photopolymn efficiency
IT Polymerization
(photochem., radical; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT Catalysts
(photochem.; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT Dyes
(pyrromethene; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT Fluorescence
Polymer networks
Polymerization kinetics
(visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT 131083-16-4, 1,3,5,7,8-Pentamethyl-2,6-diethylpyrromethene-difluoroborate
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(EMP, photosensitizer dye, initiator; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT 103-01-5, N-Phenylglycine
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(NPG, electron donor, coinitiator; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine
RL: CAT (Catalyst use); RCT (Reactant); RACT (Reactant or reagent); USES (Uses)
(TA, electron acceptor, coinitiator; visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT 24447-78-7, SR 349
RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)
(visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
IT 58738-89-9P, SR 349 homopolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(visible light photoinitiating systems, photopolymn. efficiency, and kinetics study)
RE.CNT 37 THERE ARE 37 CITED REFERENCES AVAILABLE FOR THIS RECORD
(1) Allonas, X; Eur Polym J 2001, V37, P897 CAPLUS
(2) Allonas, X; Helv Chim Acta 2001, V84, P2577 CAPLUS
(3) Allonas, X; Lasers in Chemistry, Influencing Matter 2008, V2 CAPLUS
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(20) Fouassier, J; Macromolecular engineering: from precise macromolecular synthesis to macroscopic materials properties and applications 2007, V1, P643 CAPLUS
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(28) Lovestead, T; Polymer 2005, V46, P6226 CAPLUS
(29) Monroe, B; Chem Rev 1993, V93, P435 CAPLUS
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(32) Suzuki, S; J Photochem Photobiol A: Chem 2006, V181, P181
(33) Tarzi, O; J Polym Sci, Part A: Polym Chem, under press
(34) Tulig, T; Macromolecules 1981, V14, P1501 CAPLUS
(35) Wen, M; Macromolecules 2000, V33, P9247 CAPLUS
(36) Zhu, Q; J Photochem Photobiol, A 1991, V59, P255 CAPLUS
(37) Zhu, S; Macromolecules 1990, V23, P1144 CAPLUS

REFERENCE 2

AN 153:296099 CA
TI Multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives
IN Ragain, James C., Jr.; Tiba, Amer; Charlton, David G.
PA The United States of America Dept. of Navy, USA
SO U.S. Pat. Appl. Publ., 9pp.
CODEN: USXXCO
DT Patent
LA English
INCL 523118000; 433228100
IPCI A61K0006-00 [I,A]; A61C0005-00 [I,A]
NCL 523/118.000; 433/228.100
CC 63-7 (Pharmaceuticals)
Section cross-reference(s): 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI US 20100197825	A1	20100805	US 2009-362622	20090130
PRAI US 2009-362622		20090130		

AB This invention describes an adhesive used for bonding dental and medical biomaterials to hard tissues via a mol. bridge formed from calcium-reactive amines and acrylic or methacrylic ester monomers to hard tissues such as enamel, dentin, and bone. This formulation consists of an acid-stable polymerizable compound with multifunctional acrylate crosslinkers. This formula provides good self-adherence without prior preparation of the hard tissue substrates. The formulation can contain chemical-
and/or light-activated free radical initiators.
ST multifunctional acrylate crosslinker dental biomedical adhesive
IT Dental materials and appliances
Medical goods
(adhesives; multifunctional acrylates used as crosslinkers in dental

and biomedical self-etching bonding adhesives)
IT Dental materials and appliances
(alloys; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Dental materials and appliances
(cements; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Dental materials and appliances
(ceramics; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Dental materials and appliances
(composites; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Adhesives
(medical adhesives; multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Crosslinking agents
Polymerization catalysts
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT Amines
RL: RCT (Reactant); THU (Therapeutic use); BIOL (Biological study); RACT (Reactant or reagent); USES (Uses)
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT 94-36-0, Benzoyl peroxide, biological studies 10373-78-1, Camphorquinone 75980-60-8, Diphenyl(2,4,6-trimethylbenzoyl)phosphine oxide
RL: CAT (Catalyst use); THU (Therapeutic use); BIOL (Biological study); USES (Uses)
(multifunctional acrylates used as crosslinkers in dental and biomedical self-etching bonding adhesives)
IT 97-63-2, Ethyl methacrylate 97-90-5, Ethylene glycol dimethacrylate 106-90-1, Glycidyl acrylate 106-91-2, Glycidyl methacrylate 109-16-0, Triethylene glycol dimethacrylate 140-88-5, Ethyl acrylate 619-84-1, 4-Dimethylaminobenzoic acid 689-12-3, Isopropyl acrylate 818-61-1, 2-Hydroxyethyl acrylate 925-60-0, Propyl acrylate 1070-70-8, 1,4-Butanediol diacrylate 1189-08-8, 1,3-Butanediol dimethacrylate 1565-94-2 1565-94-2, Bisgma 1830-78-0 1985-51-9, Neopentyl glycol dimethacrylate 2082-81-7, 1,4-Butanediol dimethacrylate 2210-28-8, Propyl methacrylate 2223-82-7, Neopentyl glycol diacrylate 2274-11-5, Ethylene glycol diacrylate 2399-48-6, Tetrahydrofurfuryl acrylate 2455-24-5, Tetrahydrofurfuryl methacrylate 3253-39-2 3253-41-6, Pentaerythritol tetramethacrylate 3290-92-4, Trimethylolpropane trimethacrylate 3524-66-1, Pentaerythritol trimethacrylate 3524-68-3, Pentaerythritol triacrylate 4491-03-6, biological studies 4655-34-9, Isopropyl methacrylate 4687-94-9 4986-89-4, Pentaerythritol tetracrylate 6606-59-3, 1,6-Hexanediol dimethacrylate 10287-53-3, Edmab 13048-33-4, 1,6-Hexanediol diacrylate 15625-89-5, Trimethylolpropane triacrylate 19485-03-1, 1,3-Butanediol diacrylate 24447-78-7 24448-20-2, biological studies 25584-83-2, Hydroxypropyl acrylate 25852-47-5, Polyethylene glycol dimethacrylate 26570-48-9, Polyethylene glycol diacrylate 26846-58-2, Pentaerythritol dimethacrylate 27689-12-9, biological studies 30206-34-9, Dipentaerythritol tetramethacrylate 32435-46-4, Bis[2-(methacryloyloxy)ethyl] phosphate 50853-28-6, Glycerol monomethacrylate 51989-01-6 52174-50-2, Glycerol diacrylate 52357-34-3, Glycerol monoacrylate 53417-29-1, Pentaerythritol diacrylate

56361-55-8, biological studies 56744-60-6 60506-81-2, SR399
92738-89-1, Dipentaerythritol trimethacrylate 215116-26-0,
Dipentaerythritol dimethacrylate
RL: RCT (Reactant); THU (Therapeutic use); BIOL (Biological study); RACT
(Reactant or reagent); USES (Uses)
(multifunctional acrylates used as crosslinkers in dental and
biomedical self-etching bonding adhesives)

REFERENCE 3

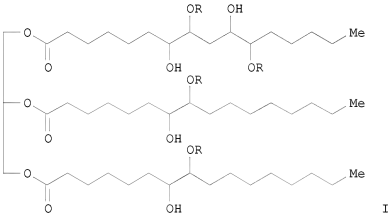
AN 153:236145 CA
TI Chemical tagging indicators for identification of overheated places in
power transformers
AU Shapovalov, L.; Figovsky, O.; Trossman, A.; Birukova, O.; Shkolnik, A.
CS Polymate Ltd - INRC, Migdal-HaEmek, Israel
SO Scientific Israel--Technological Advantages (2010), 12(1,2), 120-127
CODEN: SITAFG; ISSN: 1565-1533
PB Polymate Ltd., Israeli Research Center
DT Journal
LA English
CC 48-5 (Unit Operations and Processes)
Section cross-reference(s): 47
AB The purpose of this article is to develop chemical indicators for
identification of overheated places in power transformer with mineral oil.
The chemical indicators, which are suitable to be placed on potential trouble
spots, and release specific substances when exposed to predefined temps.
and allow early diagnostics and identification. It was elaborated
copolymers of methacrylic esters as chemical indicators in power transformers
with mineral oil. The indicators are not soluble in mineral oil.
Decomposition
of network copolymers gives high yields of methacrylate monomer (85-95%).
The monomers in mineral oil are determined by gas chromatograph. A sample of
scheme of card of applying indicators is recommended for industrial power
transformers.
ST power transformer mineral oil overheating identification chem tagging
indicator; methacrylic ester copolymer indicator power transformer oil
overheating
IT Transformer oils
(chemical tagging indicators for identification of overheated places in
power transformers)
IT Heating
(over-heating; chemical tagging indicators for identification of
overheated places in power transformers)
IT 60-00-4, reactions 80-15-9, Cumenehydroperoxide 80-43-3,
Dicumylperoxide 94-36-0, Dibenzoyl peroxide, reactions 97-63-2, Ethyl
methacrylate 97-86-9, Isobutyl methacrylate 97-88-1, Butyl
methacrylate 99-97-8, N,N-Dimethyl-p-toluidine 105-64-6 1338-23-4,
Methylethyl ketoneperoxide 2867-47-2, Dimethylaminoethyl methacrylate
10373-78-1, Camphorquinone 18358-13-9, Methacrylate, reactions
24447-78-7, SR-349 24448-20-2, SR-348
RL: RCT (Reactant); RACT (Reactant or reagent)
(chemical tagging indicators for identification of overheated places in
power transformers)
RE.CNT 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD
(1) Anon; PCT/IL 2008/00224
(2) Anon; www.hse.gov.uk/research/misc/sherzat/sum.pdf, PCT/IL 2008/00224
(3) Bamford, C; Comprehensive chemical kinetics P53

REFERENCE 4

AN 153:206507 CA
TI Acryloyl-containing coating compositions with good hardness, adhesion, transparency, and chemical resistance
IN Lee, Seong Gwon; Lee, Jeong Beom; Park, Sang Gwon
PA EP Chemtech Co., Ltd., S. Korea
SO Repub. Korean Kongkae Taeho Kongbo, 16pp.
CODEN: KRXXA7
DT Patent
LA Korean
IPCI C08L0033-08 [I,A]; C08L0033-00 [I,C*]; C08K0003-20 [I,A]; C08K0003-00 [I,C*]; C08K0005-54 [I,A]; C08K0005-00 [I,C*]; C09D0133-08 [I,A]
CC 42-7 (Coatings, Inks, and Related Products)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI KR 20100072566	A	20100701	KR 2008-131004	20081222
PRAI KR 2008-131004		20081222		

GI



I

AB Title coating compns. comprise (A) an acrylate monomer synthesized from a polyol (I) and an acrylic monomer, (B) an acrylic monomer, (3) an inorg. oxide, and (D) a silane coupling agent, wherein R = H or hydrocarbon.
ST acryloyl contg coating compn hardness adhesion transparency chem resistance
IT Polyurethanes
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(acrylates, polymers with vegetable oil acrylate; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
IT Antistatic agents
(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)
IT Soybean oil
RL: RCT (Reactant); RACT (Reactant or reagent)

(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Electric conductors
(antistatic agent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Alkali metal salts
Quaternary ammonium compounds
RL: MOA (Modifier or additive use); USES (Uses)
(antistatic agent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Coating materials
(antistatic; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Coating materials
(chemical resistant; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Transparent materials
(coatings; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Soybean oil
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(epoxidized, acrylate, polymers with acrylic monomers; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT Coating materials
(transparent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT 920-46-7DP, Methacrylic chloride, reaction products with epoxidized soybean oil 26570-48-9DP, Polyethylene glycol diacrylate, polymers with epoxidized soybean oil acrylate
RL: IMF (Industrial manufacture); POF (Polymer in formulation); PRP (Properties); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT 1070-70-8D, polymers with vegetable oil acrylate 1680-21-3D, Triethylene glycol diacrylate, polymers with vegetable oil acrylate 2223-82-7D, Neopentyl glycol diacrylate, polymers with vegetable oil acrylate 3524-68-3D, Pentaerythritol triacrylate(, polymers with vegetable oil acrylate 4986-89-4D, Pentaerythritol tetraacrylate, polymers with vegetable oil acrylate 13048-33-4D, 1,6-Hexanediol diacrylate, polymers with vegetable oil acrylate 15625-89-5D, Trimethylolpropane triacrylate, polymers with vegetable oil acrylate 24447-78-7D, polymers with vegetable oil acrylate 29570-58-9D, Dipentaerythritol hexaacrylate, polymers with vegetable oil acrylate 42978-66-5D, Tripropylene glycol diacrylate, polymers with vegetable oil acrylate 57472-68-1D, Dipropyleneglycol diacrylate, polymers with vegetable oil acrylate 60506-81-2D, Dipentaerythritol pentaacrylate, polymers with vegetable oil acrylate 94108-97-1D, Ditrimethylolpropane tetraacrylate, polymers with vegetable oil acrylate 115633-58-4D, Ditrimethylolpropane triacrylate, polymers with vegetable oil acrylate
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

IT 7601-89-0, Sodium perchlorate 7791-03-9, Lithium perchlorate
126213-51-2, Poly(3,4-ethylenedioxythiophene) 473797-97-6, Baytron PH
RL: MOA (Modifier or additive use); USES (Uses)
(antistatic agent; acryloyl-containing coating compns. with good hardness, adhesion, transparency, and chemical resistance)

REFERENCE 5

AN 153:175274 CA
TI Pyrromethene derivatives in three-component photoinitiating systems for free radical photopolymerization
AU Tarzi, O. I.; Allonas, X.; Ley, C.; Fouassier, J.-P.
CS CIHIDECAR-CONICET, Department of Organic Chemistry, FCEyN-University of Buenos Aires, Pabellon 2--Ciudad Universitaria, Buenos Aires, 1428, Argent.
SO Journal of Polymer Science, Part A: Polymer Chemistry (2010), 48(12), 2594-2603
CODEN: JPACEC; ISSN: 0887-624X
PB John Wiley & Sons, Inc.
DT Journal
LA English
CC 35-3 (Chemistry of Synthetic High Polymers)
AB 1,3,5,7,8-Pentamethyl pyrromethene difluoroborate complex (HMP) and 2,6-diethyl-8-phenyl-1,3,5,7-tetramethylpyrromethene difluoroborate complex (EPP) were used to initiate the polymerization of a diacrylate in a two-
and a three-component photoinitiating system (PIS), together with an amine (ethyl-4-dimethylaminobenzoate, EDB) and triazine A (2-(4-methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine, TA) as coinitiators. For both pyrromethene dyes, the highest conversion was achieved with the three-component PIS. As these dyes have high-fluorescence quantum yields, steady state and time-resolved techniques were used to study the possible fluorescence quenching by the amine and the triazine, as well as laser flash photolysis to investigate the electron transfer process that occurs in these PIS from either the singlet or triplet excited states. The electron transfer reaction is evidenced by using time-resolved photocond. Expts. show that the main interaction between the dye and both coinitiators is through its excited singlet state and the process is more efficient when TA is present. The beneficial effect noted when both coinitiators are used in a three-component system is ascribed to secondary reactions between the coinitiators and intermediates that lead to the generation of higher amount of initiating species and the recovery of the initial dye.
ST ethoxylated bisphenol A diacrylate radical photochem polymn catalyst kinetics
IT Polymerization
Polymerization catalysts
Polymerization kinetics
(photochem., radical; pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymn.)
IT Electron transfer
Excited singlet state
Redox potential
(pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymn.)
IT 3584-23-4, 2-(4-Methoxyphenyl)-4,6-bis(trichloromethyl)-1,3,5-triazine 10287-53-3, Ethyl-4-dimethylaminobenzoate 121207-31-6 189264-25-3

RL: CAT (Catalyst use); USES (Uses)
(pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymn.)
IT 58738-89-9P, Sartomer SR 349 homopolymer
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation)
(pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymn.)
IT 24447-78-7, Sartomer SR 349
RL: RCT (Reactant); RACT (Reactant or reagent)
(pyrromethene derivs. in three-component photoinitiating systems for free radical photopolymn.)
RE.CNT 60 THERE ARE 60 CITED REFERENCES AVAILABLE FOR THIS RECORD
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REFERENCE 6

AN 153:116641 CA
TI Overcoming the oxygen inhibition in the photopolymerization of acrylates: A study of the beneficial effect of triphenylphosphine
AU Belon, C.; Allonas, X.; Croutxe-barghorn, C.; Lalevee, J.
CS Departement de Photochimie Generale, UMR 7525 CNRS, Ecole Nationale Superieure de Chimie de Mulhouse, Universite de Haute-Alsace, Mulhouse, 68093, Fr.
SO Journal of Polymer Science, Part A: Polymer Chemistry (2010), 48(11), 2462-2469
CODEN: JPACEC; ISSN: 0887-624X
PB John Wiley & Sons, Inc.
DT Journal
LA English
CC 35-3 (Chemistry of Synthetic High Polymers)
AB Triphenylphosphine (TPP) was used in free-radical UV-curable resins to reduce oxygen inhibition effect. The relative influence of concentration, monomer viscosity, light intensity and sample thickness on TPP efficiency was investigated by real time IR spectroscopy. It is shown that TPP is an effective oxygen scavenger. The mechanism was investigated by means of Laser Flash Photolysis.
ST acrylate photopolymn kinetics triphenylphosphine oxygen scavenger
IT Polysiloxanes
RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)
(acrylates; overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)
IT Polymerization kinetics
(photochem.; overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)
IT 75980-60-8, Diphenyl-(2,4,6-trimethylbenzoyl)-phosphine oxide
RL: CAT (Catalyst use); USES (Uses)
(overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)
IT 13048-33-4 24447-78-7, Sartomer 349 42978-66-5, Tripropylene glycol diacrylate
RL: PRP (Properties); RCT (Reactant); RACT (Reactant or reagent)

(overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)
IT 603-35-0, Triphenylphosphine, uses
RL: NUU (Other use, unclassified); USES (Uses)
(oxygen scavenger; overcoming oxygen inhibition in photopolymn. of acrylates using triphenylphosphine as oxygen scavenger)
RE.CNT 38 THERE ARE 38 CITED REFERENCES AVAILABLE FOR THIS RECORD
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REFERENCE 7

AN 153:63818 CA
TI Radiation-curable resin compositions and their cured articles, coated

articles, optical films, optical lens, and optical disks, and manufacture of coated articles
IN Kawakami, Chigusa; Yamashita, Tsutomu
PA Sanyo Chemical Industries, Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 14pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IPCI C08F0020-30 [I,A]; C08F0020-00 [I,C*]; C08F0290-06 [I,A]; C08F0290-00 [I,C*]
CC 38-3 (Plastics Fabrication and Uses)
Section cross-reference(s): 37, 73, 74
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2010126670	A	20100610	JP 2008-304251	20081128

PRAI JP 2008-304251 20081128
AB Radiation-curable resin compns. contain (A) aromatic ring-containing (meth)acrylates having 20-45% aromatic ring backbone carbons and (meth)acryloyl group equiv 150-220 g/equiv and (B) photopolymn. initiators and optionally, (C) aromatic ring-free polyfunctional (meth)acrylates with functionality ≥3. Coated articles having cured articles of the compns. on substrates, such as optical films, optical lens, or optical disks, are manufactured by applying the compns. at least on one surface of the substrates, followed by irradiating a radiation. Thus, a composition comprising 10 parts 2,2'-biphenyldimethanol diacrylate with aromatic ring backbone carbon content 45% and acryloyl group equiv 161, 90 parts Epikote 828 (bisphenol A diglycidyl ether) tetraacrylate with aromatic ring backbone carbon content 24% and acryloyl group equiv 151, and 2 parts Irgacure 184 (1-hydroxycyclohexyl Ph ketone) was sandwiched between 2 pieces of Lumirror S (PET film) then irradiated with UV, the PET films being parted, to give a 5-μm thick test piece with refractive index at 25° 1.573. The composition was applied on a glass sheet, covered with Cosmoshine A 4300 (PET film) under pressure, and irradiated with UV to give a test piece showing cross-cut adhesion 0 peel/100 cuts and pencil hardness 3H.
ST UV curable acrylate resin coating optical film; lens optical UV curable acrylate; optical disk UV curable acrylate
IT Lenses
Optical disks
Optical films
(UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT Polyesters
RL: TEM (Technical or engineered material use); USES (Uses)
(UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT Epoxy resins
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylates; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT Epoxy resins
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(acrylic, crosslinked; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

IT 947-19-3, Irgacure 184
RL: CAT (Catalyst use); USES (Uses)
(UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT 24447-78-7P 55818-57-0P, Epikote 828 acrylate
RL: IMF (Industrial manufacture); POF (Polymer in formulation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT 1228454-29-2P 1228454-31-6P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT 223767-65-5P 1228454-30-5P 1228640-27-4P 1228640-99-0P
RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(crosslinked; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)
IT 25038-59-9, Cosmoshine A 4300, uses
RL: TEM (Technical or engineered material use); USES (Uses)
(film, laminate with; UV-curable resin compns. and their cured articles, coated articles, optical films, optical lens, and optical disks)

REFERENCE 8

AN 152:502755 CA
TI System and resin for rapid prototyping
IN Chapelat, Carole; Cherkaoui, Zoubair M.; Dobler, Beat; Frantz, Richard; Lagref, Jean-Jacques; Patel, Ranjana C.; Rhodes, Michael
PA Huntsman Advanced Materials (Switzerland) G.m.b.H., Switz.
SO PCT Int. Appl., 51pp.
CODEN: PIXXD2
DT Patent
LA English
IPCI B29C0067-00 [I,A]; G03F0007-038 [I,A]
IPCR B29C0067-00 [I,C]; B29C0067-00 [I,A]; G03F0007-038 [I,C]; G03F0007-038 [I,A]
CC 38-3 (Plastics Fabrication and Uses)
FAN.CNT 3

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 2010043463	A1	20100422	WO 2009-EP61958	20090915
W: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				
WO 2010043274	A1	20100422	WO 2008-EP66634	20081202

W: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

PRAI EP 2008-18228 20081017
WO 2008-EP66634 20081202

AB The invention relates to a system and a resin relating to rapid prototyping. The system comprises (a) an apparatus for producing a three-dimensional object from a light-sensitive material, wherein input optics (IO) and output optics (OO) facilitates transmission of light emitted from an illumination source via individually controllable light modulators (LM) of spatial light modulator (SLM) to an illumination area (IA), wherein said (OO) enable focusing of the pattern of light from said (SLM) on said (IA); and (b) a resin composition comprising (A) an acrylate component with (B) a methacrylate component and (C) a photoinitiator.

ST three dimensional object prodn system prototyping

IT Polyurethanes
RL: TEM (Technical or engineered material use); USES (Uses)
(methacrylates; system and resin for rapid prototyping)

IT Catalysts
(photochem.; system and resin for rapid prototyping)

IT Stabilizing agents
(system and resin for rapid prototyping)

IT 41637-38-1, Sartomer 348C
RL: TEM (Technical or engineered material use); USES (Uses)
(SR 348C; system and resin for rapid prototyping)

IT 42594-17-2, Sartomer 833S
RL: TEM (Technical or engineered material use); USES (Uses)
(SR 833S; system and resin for rapid prototyping)

IT 24650-42-8, Irgacure 651 75980-60-8, Lucirin TPO
RL: CAT (Catalyst use); USES (Uses)
(system and resin for rapid prototyping)

IT 7803-49-8D, Hydroxy amine, N-nitroso complex
RL: MOA (Modifier or additive use); USES (Uses)
(system and resin for rapid prototyping)

IT 24447-78-7, Sartomer 349 26403-58-7 26570-48-9, Sartomer 344 178153-95-2, Craynor CN 981 345295-25-2, Genomer 4205
RL: TEM (Technical or engineered material use); USES (Uses)
(system and resin for rapid prototyping)

RE.CNT 4 THERE ARE 4 CITED REFERENCES AVAILABLE FOR THIS RECORD
(1) Chikaoka Satoyuki; US 6130025 A 2000 CAPLUS
(2) Dicon As; WO 0021735 A1 2000
(3) Michae, R; WO 2005092598 A1 2005 CAPLUS
(4) Smith Jeffrey M; US 6500378 B1 2002 CAPLUS

REFERENCE 9

AN 152:478559 CA
TI Adhesive composition and adhesion method

IN Hisha, Yuki; Yoda, Kimihiko; Oshima, Kazuhiro
PA Denki Kagaku Kogyo Kabushiki Kaisha, Japan
SO PCT Int. Appl., 22pp.
CODEN: PIXXD2
DT Patent
LA Japanese
IPCI C08L0033-00 [I,A]; C08K0003-10 [I,A]; C08K0003-00 [I,C*]; C08K0005-07 [I,A]; C08K0005-17 [I,A]; C08K0005-00 [I,C*]; C08L0009-02 [I,A]; C08L0009-00 [I,C*]; C09J0004-02 [I,A]; C09J0005-00 [I,A]; C09J0011-06 [I,A]; C09J0011-02 [I,C*]; C09J0109-02 [I,A]; C09J0109-00 [I,C*]; C09J0133-04 [I,A]
IPCR C08L0033-00 [I,C]; C08L0033-00 [I,A]; C08K0003-00 [I,C]; C08K0003-10 [I,A]; C08K0005-00 [I,C]; C08K0005-07 [I,A]; C08K0005-17 [I,A]; C08L0009-00 [I,C]; C08L0009-02 [I,A]; C09J0004-02 [I,C]; C09J0004-02 [I,A]; C09J0005-00 [I,C]; C09J0005-00 [I,A]; C09J0011-02 [I,C]; C09J0011-06 [I,A]; C09J0109-00 [I,C]; C09J0109-02 [I,A]; C09J0133-04 [I,C]; C09J0133-04 [I,A]
CC 38-3 (Plastics Fabrication and Uses)
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI WO 2010041710	A1	20100415	WO 2009-JP67543	20091008

W: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, SE, SI, SK, SM, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

PRAI JP 2008-262015 20081008
AB Disclosed is a high-speed-curing and moisture-resistant adhesive composition Title composition comprises a first preparation comprising (A) a nitrile rubber, (B) a (meth)acrylic composition, (C) a compound having an enal structure or (D) an amine compound, and (F) a radical polymerization initiator; and a second preparation comprising (A) a nitrile rubber, (B) a (meth)acrylic composition, (D) an amine compound or (C) an enal compound, and (E) a compound containing copper.
ST adhesive compn two component; nitrile rubber acrylic polymer adhesive amine enal curing aid
IT Naphthenic acids
RL: MOA (Modifier or additive use); USES (Uses)
(copper salts; two-package adhesive composition and adhesion method)
IT Adhesives
(two-component; two-package adhesive composition and adhesion method)
IT Acrylic polymers
Nitrile rubber
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(two-package adhesive composition and adhesion method)
IT 1709-70-2, 1,3,5-Trimethyl-2,4,6-tris(3,5-di-tert-butyl-4-hydroxybenzyl)benzene

RL: MOA (Modifier or additive use); USES (Uses)
(antioxidant; two-package adhesive composition and adhesion method)
IT 9003-18-3
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(nitrile rubber; two-package adhesive composition and adhesion method)
IT 62-53-3, Aniline, uses 645-62-5, 2-Ethyl-2-hexenal 20543-04-8, Copper octanoate
RL: MOA (Modifier or additive use); USES (Uses)
(two-package adhesive composition and adhesion method)
IT 79-10-7D, Acrylic acid, polymers 79-41-4D, Methacrylic acid, polymers 3290-92-4D, Trimethylolpropane trimethacrylate, polymers 5888-33-5D, Isobornyl acrylate, polymers 7534-94-3D, Isobornyl methacrylate, polymers 9003-56-9, Acrylonitrile-butadiene-styrene copolymer 15625-89-5D, Trimethylolpropane triacrylate, polymers 24447-78-7D, polymers 24448-20-2D, polymers, uses 41637-38-1D, Bisphenol A-ethylene oxide adduct dimethacrylate, polymers 64401-02-1D, Bisphenol A-ethylene oxide adduct diacrylate, polymers 107080-92-2, Butadiene-methyl methacrylate-styrene graft copolymer 1200973-80-3
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(two-package adhesive composition and adhesion method)
RE.CNT 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD
(1) Denki Kagaku Kogyo Kabush 1 ki Kaisha; WO 2008108273 A1 2008 CAPLUS
(2) Ministro Dell Universita' e Delia Ricerca Scientif l ca e Technologica; US 5283292 A1 1994 CAPLUS
(3) Ministro Dell Universita' e Delia Ricerca Scientif l ca e Technologica; EP 540098 A1 1994 CAPLUS
(4) Ministro Dell Universita' e Delia Ricerca Scientif l ca e Technologica; JP 6248238 A 1994
(5) Okura Industrial Co Ltd; JP 5125331 A 1993
(6) Okura Industrial Co Ltd; JP 2003165806 A 2003 CAPLUS

REFERENCE 10

AN 152:466143 CA
TI Presensitized lithographic plates and manufacture of lithographic plates therefrom
IN Sasaki, Tomoya; Ohashi, Hidekazu
PA Fujifilm Corporation, Japan
SO Jpn. Kokai Tokkyo Koho, 63pp.
CODEN: JKXXAF
DT Patent
LA Japanese
IPCI G03F0007-027 [I,A]; G03F0007-004 [I,A]; G03F0007-00 [I,A]
IPCR G03F0007-027 [I,C]; G03F0007-027 [I,A]; G03F0007-00 [I,C]; G03F0007-00 [I,A]; G03F0007-004 [I,C]; G03F0007-004 [I,A]
CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 35, 38
FAN.CNT 1

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI JP 2010079085	A	20100408	JP 2008-249138	20080926

PRAI JP 2008-249138 20080926
AB The presensitized lithog. plates have, on supports, photosensitive layers containing (A) compds. having groups chosen from R2R3C:CR1[C(:O)NR4],

R5R5C:C(CONR7R8), and/or R10R11C:CR9[C(:O)N] (R1-R3, R5, R6, R9-R11 = H, alkyl, aryl; R4, R7, R8 = H, alkyl, aryl, aralkyl, alkenyl, heterocyclic), (B) polymerization initiators, (C) polymerizable compds. other than A, and (D) binder polymers, at A/C weight ratio 0.02-4. The presensitized lithog. plates are exposed and then developed by developers with pH 2-10 to remove unexposed parts. The presensitized lithog. plates have high development speed, printability, and initial and long-term soiling resistance.

ST neg presensitized lithog plate acrylamide monomer ratio developability printability; soiling resistance neg presensitized lithog plate

IT Polyoxyalkylenes
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(acrylic, graft, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Polyvinyl butyrals
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Lithographic plates
(neg.-working presensitized; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Allylic compounds
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Lithography
(platemaking; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Polyurethanes
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(polyoxyalkylene-, block, acrylates, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT Aromatic compounds
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(vinyl, other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 28679-16-5, Trimethylhexamethylene diisocyanate
RL: RCT (Reactant); RACT (Reactant or reagent)
(2,2,4- and 2,4,4-mixture, in preparation of acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 1220748-62-8P 1220748-63-9P

RL: IMF (Industrial manufacture); PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PREP (Preparation); PROC (Process); USES (Uses)
(acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 959-52-4 1187-59-3 39573-27-8 143785-80-2 160432-07-5
1045850-44-9 1220748-64-0 1220748-67-3
RL: PEP (Physical, engineering or chemical process); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(acrylamide monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 170211-39-9 1140463-33-7
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(assumed monomers, binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 59049-11-5
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); PRPH (Prophetic); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 9002-89-5 25086-15-1 65697-22-5 709037-26-3 915977-69-4
1126184-48-2 1160246-70-7
RL: PEP (Physical, engineering or chemical process); POF (Polymer in formulation); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(binders; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 1220748-58-2P 1220748-59-3P 1220748-60-6P 1220748-61-7P
RL: IMF (Industrial manufacture); RCT (Reactant); PREP (Preparation); RACT (Reactant or reagent)
(in preparation of acrylamide monomers; presensitized lithog. plates containing
acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 10029-04-6, Ethyl 2-(hydroxymethyl)acrylate
RL: RCT (Reactant); RACT (Reactant or reagent)
(in preparation of acrylamide monomers; presensitized lithog. plates containing
acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 60506-81-2, SR 399
RL: PEP (Physical, engineering or chemical process); PRPH (Prophetic); TEM (Technical or engineered material use); PROC (Process); USES (Uses)
(other monomers; presensitized lithog. plates containing acrylamide monomers and other monomers at prescribed ratio in photosensitive layers and manufacture of lithog. plates therefrom)

IT 1025-15-6, TAIC 24447-78-7 40220-08-4 41137-60-4 74389-53-0
128738-52-3
RL: PEP (Physical, engineering or chemical process); TEM (Technical or

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     engineered material use); PROC (Process); USES (Uses)
        (other monomers; presensitized lithog. plates containing acrylamide
        monomers and other monomers at prescribed ratio in photosensitive
        layers and manufacture of lithog. plates therefrom)
IT   1220748-68-4
     RL: PEP (Physical, engineering or chemical process); TEM (Technical or
     engineered material use); PROC (Process); USES (Uses)
        (presensitized lithog. plates containing acrylamide monomers and other
        monomers at prescribed ratio in photosensitive layers and manufacture of
        lithog. plates therefrom)


=> D HIS

     (FILE 'HOME' ENTERED AT 15:03:12 ON 19 OCT 2010)

     FILE 'REGISTRY' ENTERED AT 15:03:23 ON 19 OCT 2010
L1            0 S 64404-02-4
L2            6 S SARTOMER 349
L3            0 S SARTOMER 349/CRN
L4            1 S SARTOMER 349/CN

=> S EBECRYL 8402
          2092 EBECRYL
           238 8402
L5          76 EBECRYL 8402
                (EBECRYL(W)8402)

=> S EBECRYL 8402/CN
L6            1 EBECRYL 8402/CN

=> D

L6   ANSWER 1 OF 1  REGISTRY  COPYRIGHT 2010 ACS on STN
RN   183449-62-9  REGISTRY
ED   Entered STN:  27 Nov 1996
CN   Ebecryl 8402  (CA INDEX NAME)
OTHER NAMES:
CN   EB 8402
CN   EBC 8402
CN   Ebecryl EB 8402
ENTE An aliphatic urethane acrylate (Cray Valley)
MF   Unspecified
CI   PMS, COM, MAN
PCT  Manual registration
SR   CA
LC   STN Files:   CA, CAPLUS, TOXCENTER, USPAT2, USPATFULL

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***
               38 REFERENCES IN FILE CA (1907 TO DATE)
                9 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
               38 REFERENCES IN FILE CAPLUS (1907 TO DATE)


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     (FILE 'HOME' ENTERED AT 15:03:12 ON 19 OCT 2010)
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     FILE 'REGISTRY' ENTERED AT 15:03:23 ON 19 OCT 2010
L1             0 S 64404-02-4
L2             6 S SARTOMER 349
L3             0 S SARTOMER 349/CRN
L4             1 S SARTOMER 349/CN
L5            76 S EBECRYL 8402
L6             1 S EBECRYL 8402/CN

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COST IN U.S. DOLLARS                                SINCE FILE      TOTAL
                                                         ENTRY    SESSION
FULL ESTIMATED COST                                      50.63      50.85

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)          SINCE FILE      TOTAL
                                                         ENTRY    SESSION
CA SUBSCRIBER PRICE                                      -0.80      -0.80

STN INTERNATIONAL LOGOFF AT 15:05:17 ON 19 OCT 2010
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